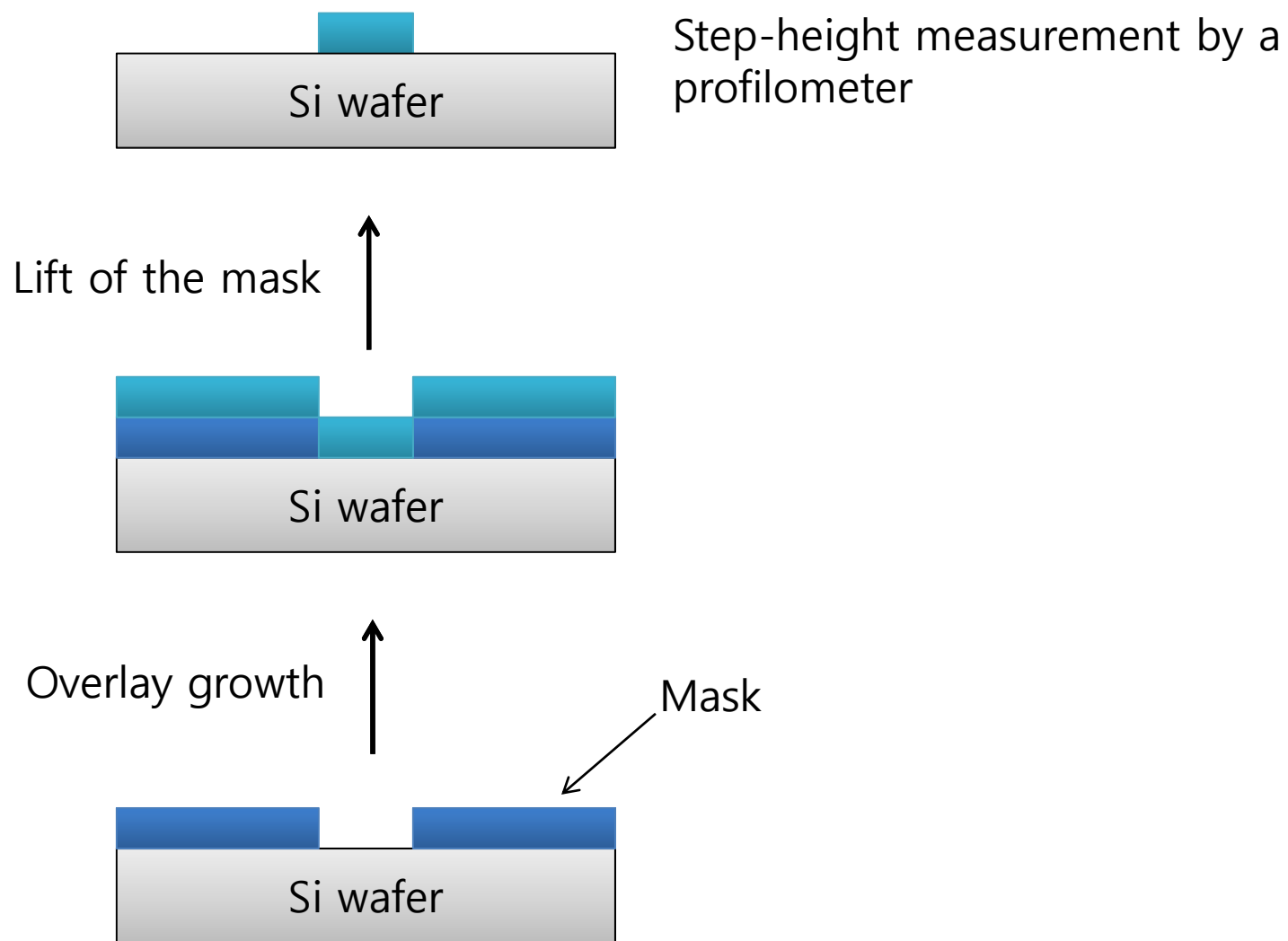


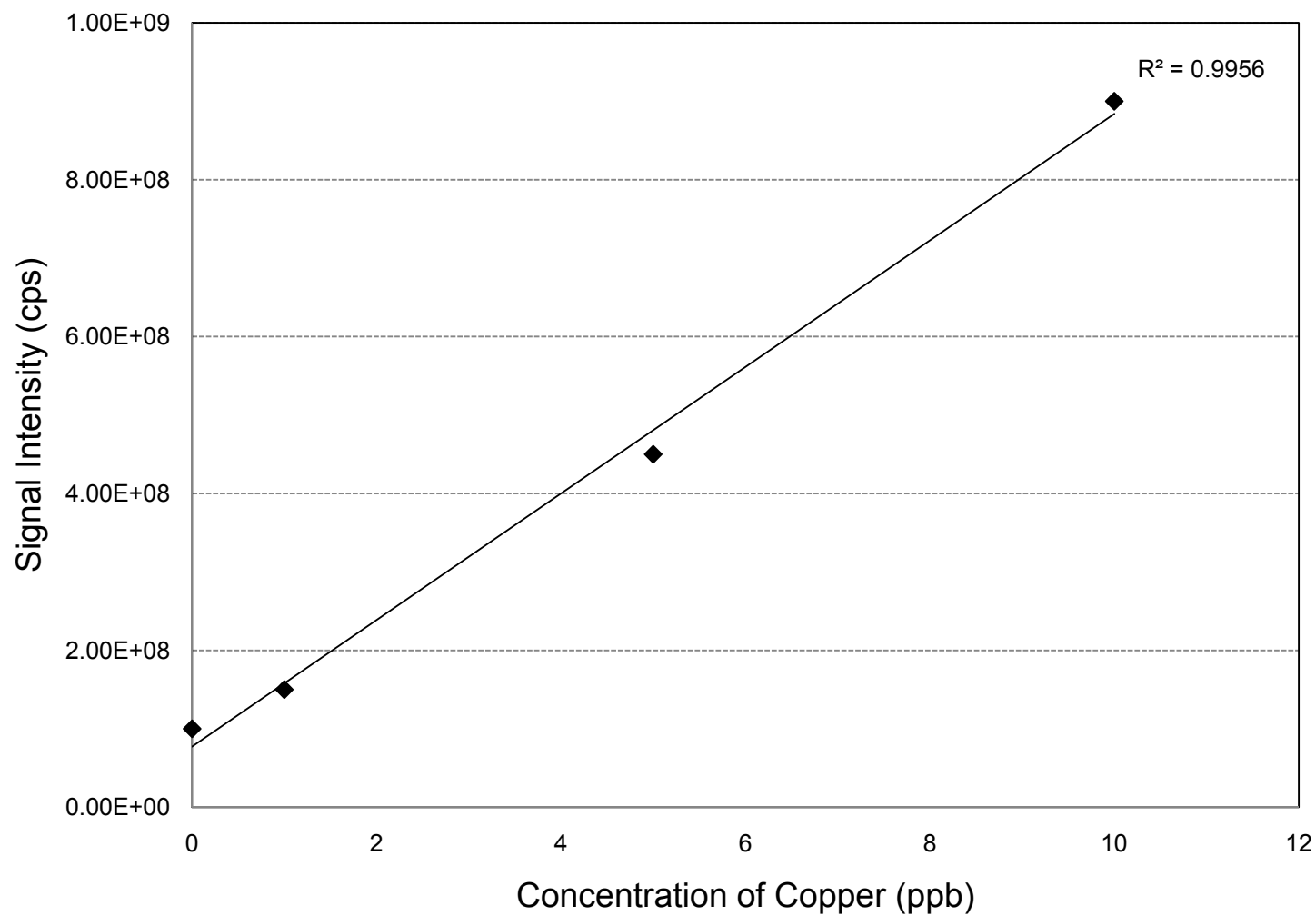
Supplementary Figures for:

**Laser ablation ICP-MS to determine Cu on a Si
Wafer prepared by ion sputtering**

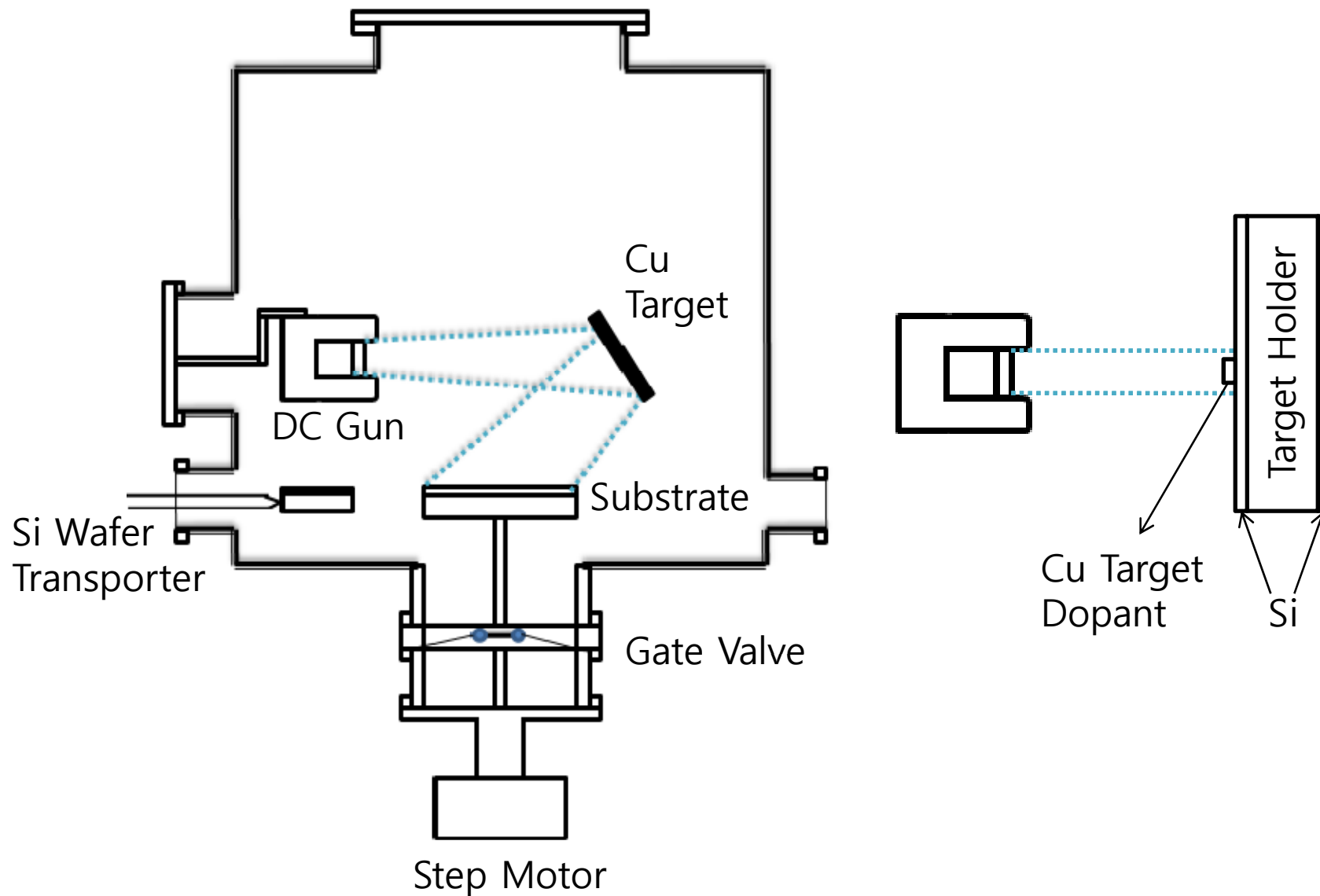
J. S. Lee and H. B. Lim



Thickness measurement for deposition rate

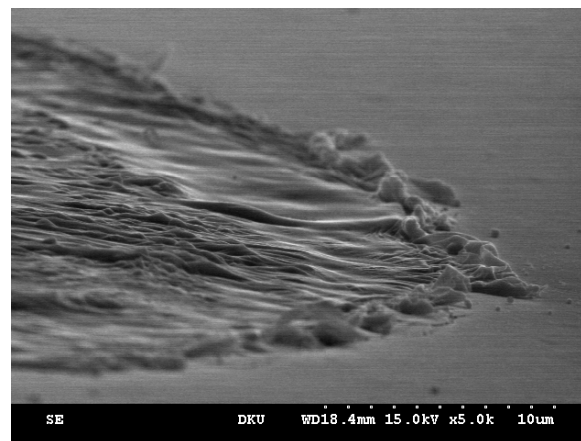
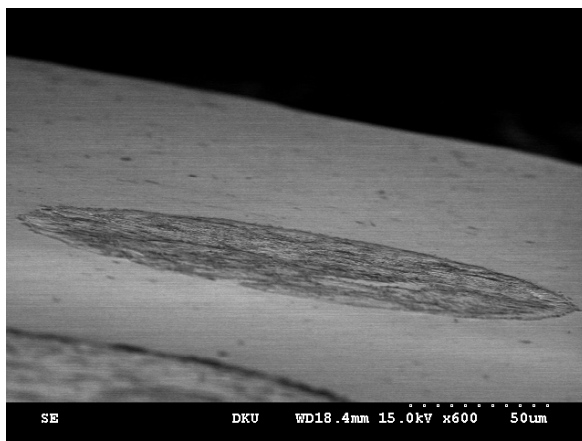


The standard addition calibration curve for NIST SRM616.
The correlation coefficient was around 0.9956.

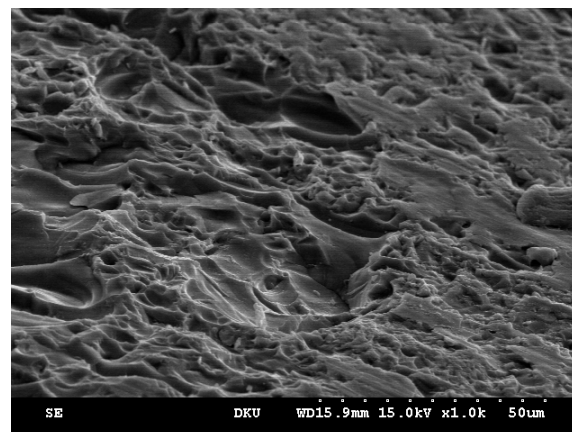
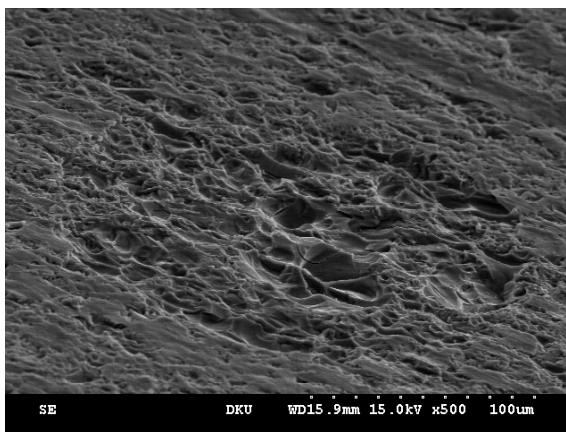


The typical ion sputtering system.

a)



b)



SEM images of ablated craters for Si wafer a) and NIST glass b):
one laser shot was made for a) and 5 laser shots for b).